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(54) Title: NON-COVALENTLY CROSSLINKABLE MATERIALS FOR PHOTOLITHOGRAPHY PROCESSES

(57) Abstract: This invention describes compositions and methods of using non-covalently crosslinked resin coatings for litho-
graphic applications. These materials are designed to undergo, after coating, a change that provides solvent resistance and, with
some materials, simultaneous aqueous-base solubility. Non-covalent interactions allow for easier removal of these coatings than of
covalently crosslinked materials. These types of materials are well-suited for trench and gap fill applications, as well as for anti-re-
flective coatings, spin-on carbon layers, and etch masks.



WO 2009/018217 A3